

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	35035	(single adj crystal) near5 (layer or film or coat\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:09
L2	514	1 and (wafer near5 (test\$6 or reusable or reused or reclaim\$6 or (re adj (used or usable or claim\$6))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:10
L3	496	2 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:10
L4	330	3 and ((test\$6 or check\$6 or monitor\$6 or inspect\$6 or measur\$6 or calibrat\$6 or validat\$6 or evaluat\$6 or detect\$6 or verif\$3) near10 (process\$6 or tool or apparatus or chamber or reactor or vessel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:11
L5	318	4 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:11
L6	295	5 and (coat\$6 or deposit\$6) and (remov\$6 or refresh\$6 or replac\$6 or recondition\$6 or (re adj (mov\$6 or fresh\$6 or replac\$6 or condition\$6)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 18:12

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	24270	wafer near5 (test\$6 or reusable or reused or reclaim\$6 or (re adj (used or usable or claim\$6)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:08
L5	198	4 same (single adj crystal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:09
L6	180	5 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:09
L7	107	6 and ((test\$6 or check\$6 or monitor\$6 or inspect\$6 or measur\$6 or calibrat\$6 or validat\$6 or evaluat\$6 or detect\$6 or verif\$3) near10 (process\$6 or tool or apparatus or chamber or reactor or vessel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:10

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	25692	(test\$6 or check\$6 or monitor\$6 or inspect\$6 or measur\$6 or calibrat\$6 or validat\$6 or evaluat\$6 or detect\$6 or verif\$3) near10 (tool or apparatus or chamber or reactor or vessel) near10 semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:04
L2	245	L1 and (((polysilicon or polySi or (poly adj (Si or silicon)))) near15 (polish\$6 or CMP)) or (single adj crystal)) same wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:04
L3	230	L2 and (@ad<"20031119" or @rlad<"20031119")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/08 17:04